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ISSUE CLASS:

## U.S. UTILITY Patent Application

MR O.I.P.E. PATENT DATE  
SCANNED 641 Q.A. 2001

APPLICATION NO. 09/885744	CONT/PRIOR	CLASS 438	SUBCLASS	ART UNIT <del>2872</del> 2872	EXAMINER K. MALLON
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**TITLE**

## Method for annealing ultra-thin, high quality gate oxide layers using oxidizer/hydrogen mixtures

PTO-2040  
12/99[illegible]

<input type="checkbox"/> <b>TERMINAL DISCLAIMER</b>	<b>DRAWINGS</b>		<b>CLAIMS ALLOWED</b>	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.	_____ (Assistant Examiner) (Date)		<b>NOTICE OF ALLOWANCE MAILED</b>	
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____ _____ _____	_____ (Primary Examiner) (Date)		<b>ISSUE FEE</b>	
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